



Abstract

The continuous growth of academic interest for nano-fabrication topic since the mid-90's is also observed in the steady growth of granted patents and gives hope for a future potential industrial applicability.

The gas aggregation process is a pertinent process, overcoming the limitations of both wet-chemical methods and of mask lithography (speed, deposition area). This process can be combine with standard vacuum deposition processes and integrated into standard vacuum deposition tools, but must be up-scaled to large-area deposition for industrial applications.

extension (Magnetron Sputtering Matrix deposition or CNT deposition by ESI)

20mm wide nanoparticle deposition.

After presenting the technical setup and its operation principle, this work will show obtained results for the deposition of Ag NP